

ABSTRACT

The exposure apparatus comprises a projection optical system that has an image field capable of exposing a shot area in a scanning exposure apparatus in one shot. This allows a
5 1 in 1 exposure, with the shot area being the maximum exposable range of the scanning exposure apparatus. In addition, the main control unit changes the control factor of the exposure system contributing to the throughput, in accordance with the minimum line width of the pattern. The control factor is
10 changed so that the state (or the value) moves into a state where more priority is put on throughput, only when reduction in exposure accuracy is allowed. This makes it possible to improve the throughput while maintaining the exposure accuracy, compared with the case when the exposure system is controlled
15 based on the same value at all times.